

Modern PV-Technologies

3.1: Solar cell materials

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- Absorbers (semiconductor)
 - c-Si (best compromise btw. cost and efficiency)
 - CIGS, CdTe (high efficiency, potential bottleneck rare materials)
 - Organic, dye, perovskite (under research)
 - GaAs + III-V (highest efficiency, highest cost)
 - Thin film silicon (moderate efficiency, large area)
- Contacts (metals, TCOs)
 - Ag (reflectivity, conductivity)
 - Al (normally high reflectivity, but...)
 - $\text{In}_2\text{O}_3:\text{SnO}_2$ (ITO, rare element In)
 - ZnO (unstable with acids/bases)
 - $\text{SnO}_2:\text{F}$ (FTO, poor transparency)

Absorption in a medium

Wave vector in medium defined with refractive index $n + i\kappa$

$$k = \frac{2\pi}{\lambda_{eff}} = \frac{2\pi}{\lambda_0} (n + i\kappa) = \frac{2\pi}{\lambda_0} \sqrt{\epsilon}$$

Field amplitude and intensity:

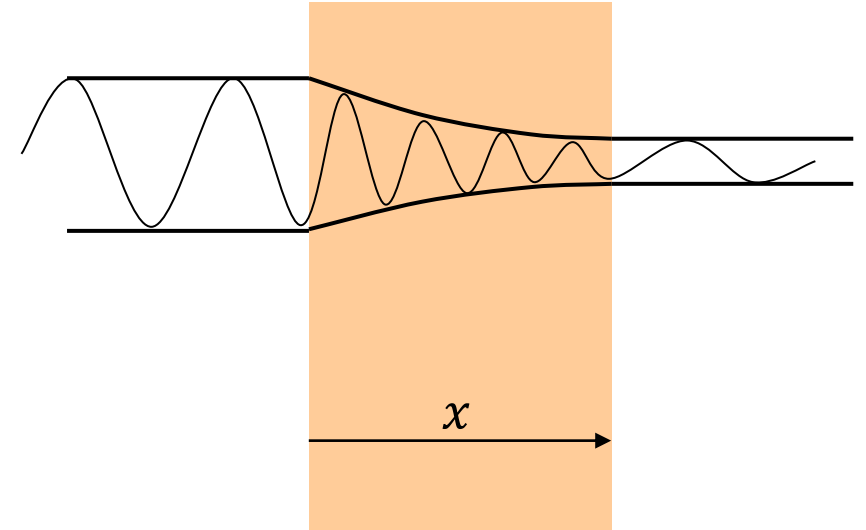
$$E(x, t) = E_0 \exp\{i((n + i\kappa)k_0x - \omega t)\}$$

$$\begin{aligned} |E(x, t)|^2 &= |E_0 \exp\{i((n + i\kappa)k_0x - \omega t)\}|^2 \\ &= |E_0|^2 \exp\{-\underbrace{(2\kappa \cdot 2\pi/\lambda)}_{\alpha} x\} \end{aligned}$$

Absorption coefficient: exponential decay of intensity

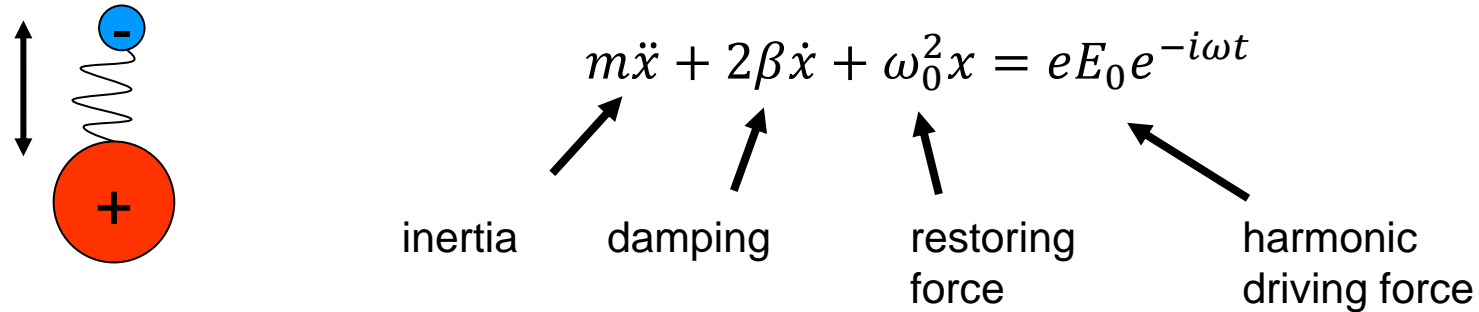
$$\alpha = 4\pi\kappa / \lambda$$

Issue: how to find n or ϵ



Dispersion (frequency dependence)

A (very) simple model for atoms in a solid: oscillator with damping
e.g. movement of electrons against cores



Average amplitude of driven oscillator

$$x_0 = \frac{eE_0}{m} (-\omega^2 - 2i\beta\omega + \omega_0^2)$$

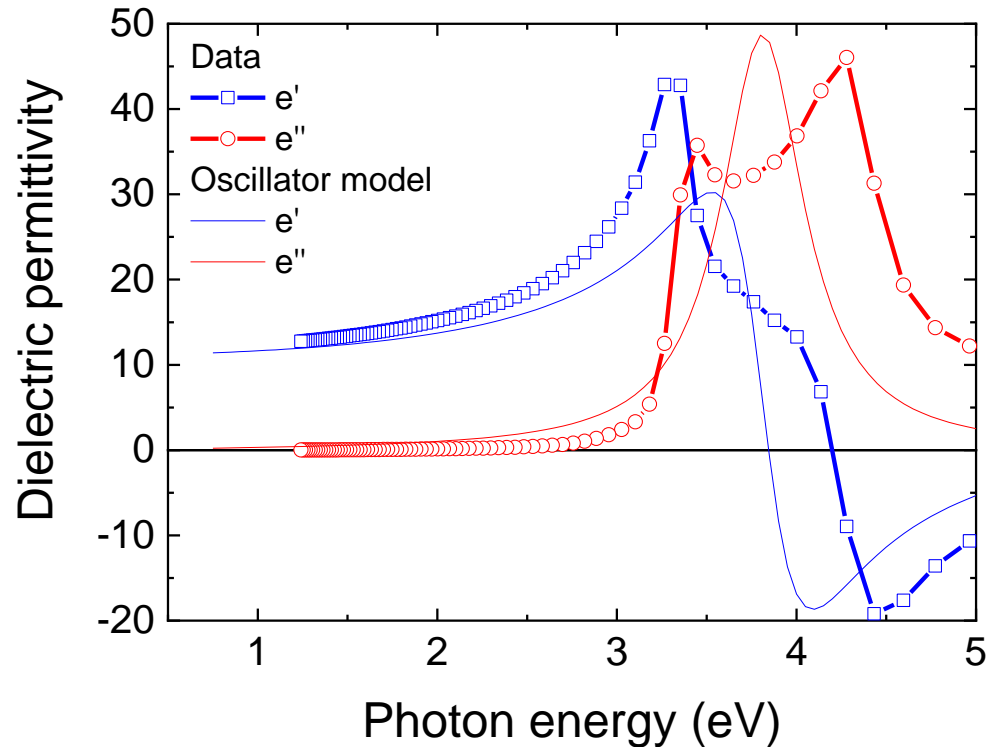
Dipole moment and macroscopic polarization:

$$P = \frac{N}{V} p = \frac{N}{V} e x_0 = \epsilon_0 (\epsilon - \epsilon_\infty) E$$

Find dielectric function:

$$\epsilon(\omega) = (n + ik)^2 = \epsilon_\infty + \underbrace{\frac{e^2 N}{\epsilon_0 m V} \frac{1}{(\omega_0^2 - 2i\beta\omega - \omega^2)}}_{\chi \text{ (susceptibility)}}$$

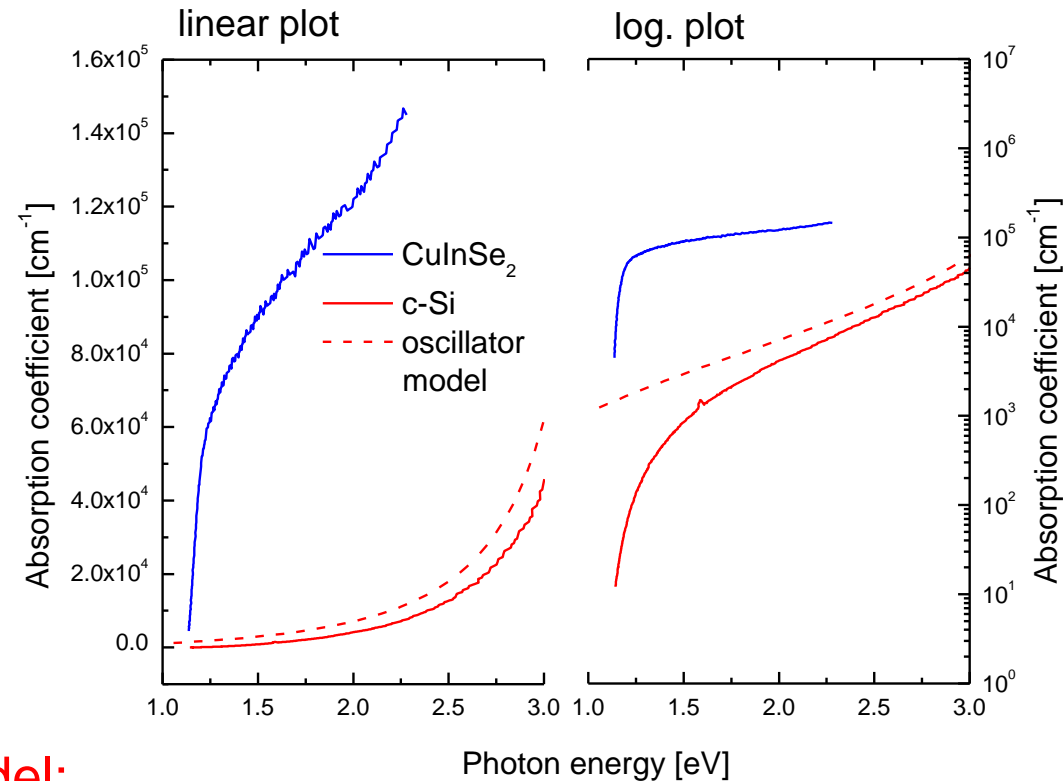
Comparison to measured dispersion



The primitive model with one oscillator yields dispersion effects
 Two oscillators (or more) can yield better correspondence (χ is additive!)

Data: c.f. Green, SEM (2008)

Absorption coefficient (measured)



Oscillator model:

- OK for c-Si on lin. scale
- BUT no gap behaviour (c.f. log scale!)
- fails totally for CIGS

Absorption coefficient of semiconductors

Needs quantum mechanics

Heuristic link between ϵ'' and absorption:

$$P_{abs} = \underbrace{\frac{1}{2} \omega \epsilon_0 \epsilon'' E_0 E_0^*}_{\text{Absorbed power from Poynting theorem}} = \underbrace{\hbar \omega \sum_{\vec{k}, \vec{k}'} w_{vc}}_{\text{Absorbed power by summing all allowed quantum-mechanical transitions}}$$

Absorbed power
from Poynting
theorem

Absorbed power by summing
all allowed quantum-mechanical
transitions

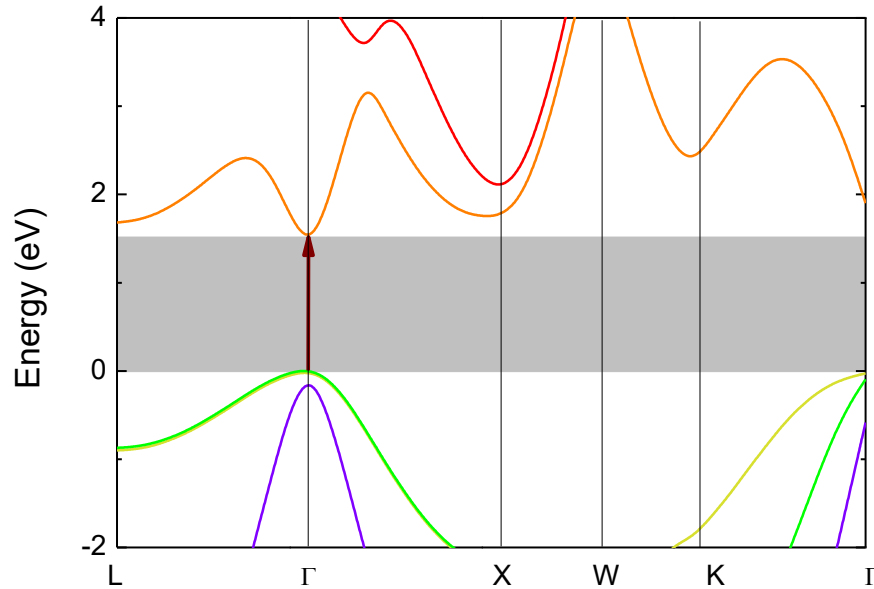
solve for ϵ'' , determine ϵ' via Kramers-Krönig relation

$$\epsilon'(\omega) = 1 + \frac{2}{\pi} \cdot \mathcal{P} \int_0^{\infty} \frac{\omega' \cdot \epsilon''(\omega')}{\omega'^2 - \omega^2} d\omega'$$

More precise derivation with density operator: Adler, Phys. Rev. (1962)

Direct absorption (e.g. GaAs)

Band diagram (pseudopotential method)



Interaction Hamiltonian:
electron-radiation

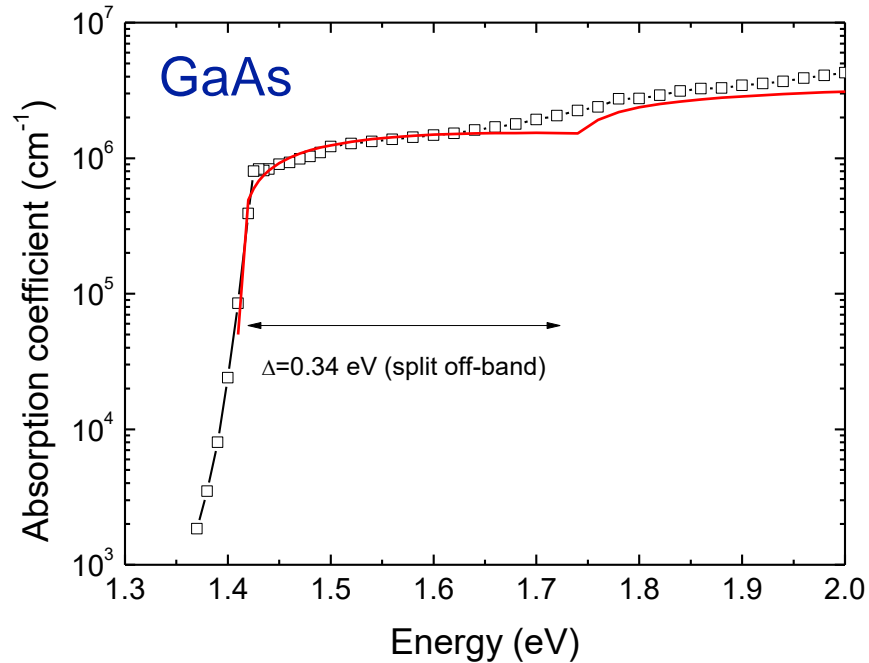
$$H' = H_{er} = -\frac{e}{m} \vec{A} \vec{p}$$

(neglect $|\vec{A}|^2$ term)

Transition probability:
Fermi's Golden rule

$$w_{vc} = \left| \left\langle c\vec{k}' \left| -\frac{e}{m} \vec{A} \vec{p} \right| v\vec{k} \right\rangle \right|^2 \cdot \frac{2\pi}{\hbar} \delta(E_c(\vec{k}) - (E_v(\vec{k}') + \hbar\omega))$$

details of derivation: see e.g. Hamaguchi, Basic Semiconductor Physics



$$\epsilon'' = \begin{cases} 0 & \text{for } \hbar\omega < E_g \\ \frac{e^2 p_{vc}^2}{2\pi\epsilon_0 m^{*2} \omega^2} \sqrt{\frac{8m^{*3}}{\hbar^6} (\hbar\omega - E_g)} & \text{for } \hbar\omega > E_g \end{cases}$$

+ term of split-off band for $\hbar\omega > E_g + \Delta E_{so}$

$$\epsilon'' = 2 \cdot n\kappa$$

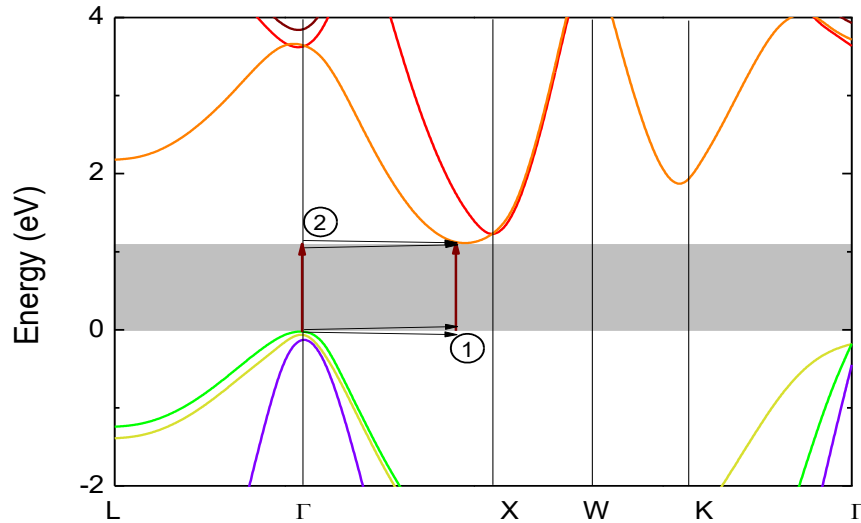
$$\alpha = 4\pi \cdot \kappa / \lambda \sim \frac{1}{\omega} \sqrt{\hbar\omega - E_g}$$

Proportional to square root!

Direct gaps: generally high absorption $\sim 10^6 \text{ cm}^{-1}$ close to gap

Indirect absorption (e.g. Silicon)

Band diagram



Interaction Hamiltonian:
electron-radiation + electron-lattice

$$H' = H_{er} + H_{el}$$

$$H_{er} = -\frac{e}{m} \vec{A} \vec{p}$$

Deformation
potential

$$H_{el} = D_V \cdot \nabla \vec{u} =$$

$$= D_V \sqrt{\frac{\hbar}{2M\omega_q}} \cdot (i\vec{e}_{\vec{q}} \vec{q}) (a \cdot e^{i\vec{q}\vec{r}} - a^\dagger \cdot e^{-i\vec{q}\vec{r}})$$

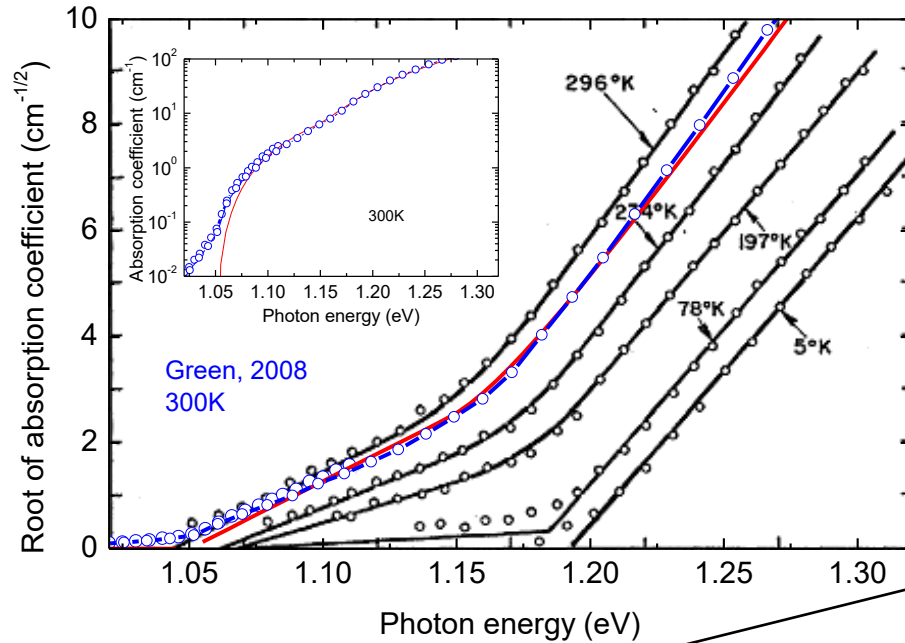
Fermi's Golden rule
(second order)

$$w_{if} = \left| \sum_m \frac{\langle f | H_{er} + H_{el} | m \rangle \langle m | H_{er} + H_{el} | i \rangle}{E_m - E_i} \right|^2 \cdot \frac{2\pi}{\hbar} \delta(E_f - E_i)$$

Integrated:

$$\epsilon'' \sim \frac{4\pi e^2}{\epsilon_0 \omega^2 m^2} \cdot \frac{2}{(2\pi)^4} \sqrt{\frac{64 m_e^{*3} m_h^{*3} \pi}{\hbar^{12}}} \frac{\pi}{8} (\hbar\omega \pm \hbar\omega_{\vec{q}} - E_g)^2 \frac{\hbar}{2m\omega_q} \left(n \pm \frac{1}{2} + \frac{1}{2} \right)$$

Absorption coefficient c-Si



Phonon population
 $\hbar\omega_{\vec{q}} \approx 55 \text{ meV}$

$$\alpha(h\nu) \sim \frac{1}{\omega} \left[\left(\frac{1}{e^{\frac{\hbar\omega_{\vec{q}}}{kT}} - 1} \right) (\hbar\omega + \hbar\omega_{\vec{q}} - E_g)^2 + \left(\frac{1}{e^{\frac{\hbar\omega_{\vec{q}}}{kT}} - 1} + 1 \right) (\hbar\omega - \hbar\omega_{\vec{q}} - E_g)^2 \right]$$

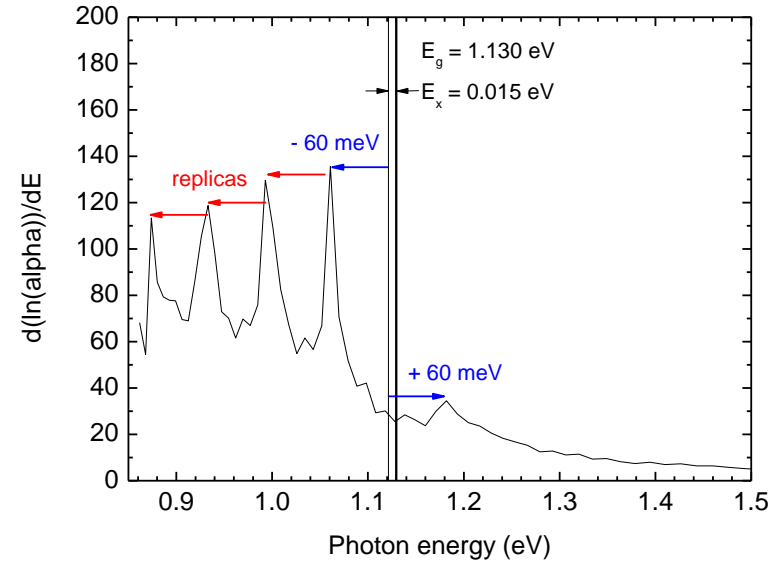
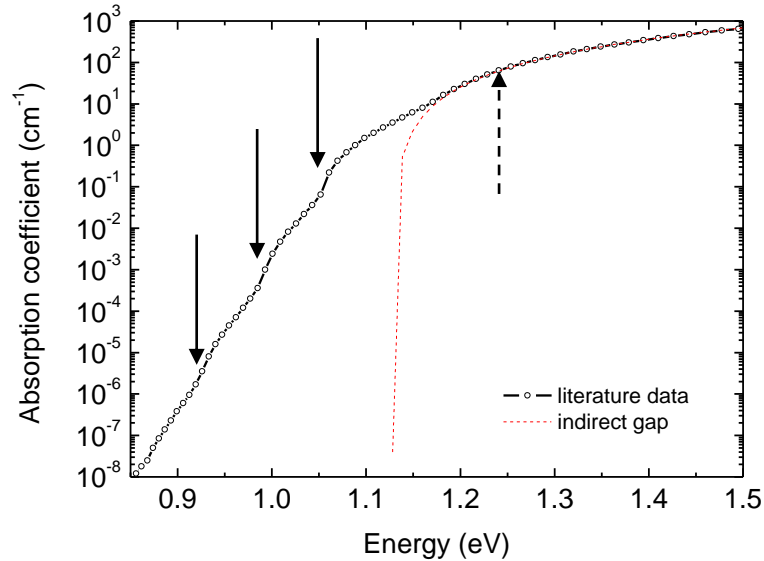
(lattice provides phonon)

(lattice absorbs phonon)

Excellent correspondence to measured data

MacFarlane, PR 1955
 Braunstein, PR 1959

Close-up of low absorption region



Weakly absorbing tail below gap

Fine structure:

- large signatures at $\pm 60 \text{ meV}$
- weak signatures at $\pm 20 \text{ meV}$

Explanation: LO and TO phonons

mediate absorption

below gap: lattice must provide phonons (cooling)

above gap: phonons are emitted (heating)

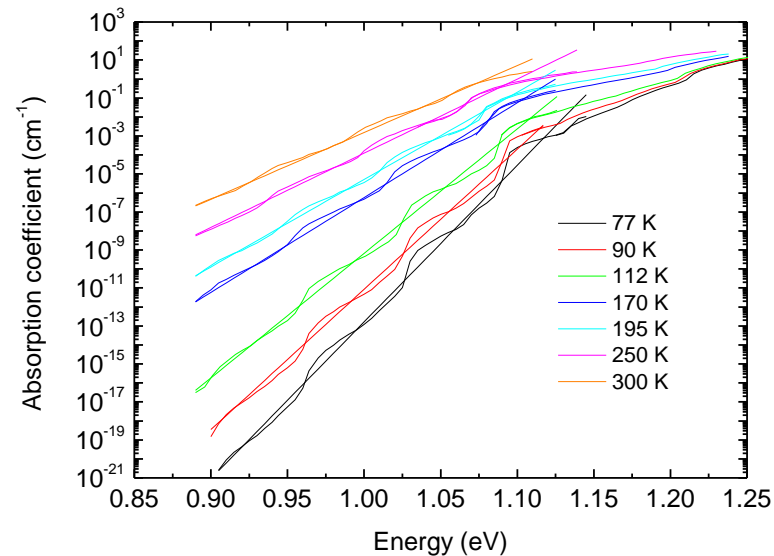
Haynes, JPCS 1959

Vouk, JPC 1977

Cody, JNCS 1992

Close up: sub-gap absorption

Temperature dependence of ultra-low absorption:
(use generalized Planck radiation law to invert photoluminescence yield)

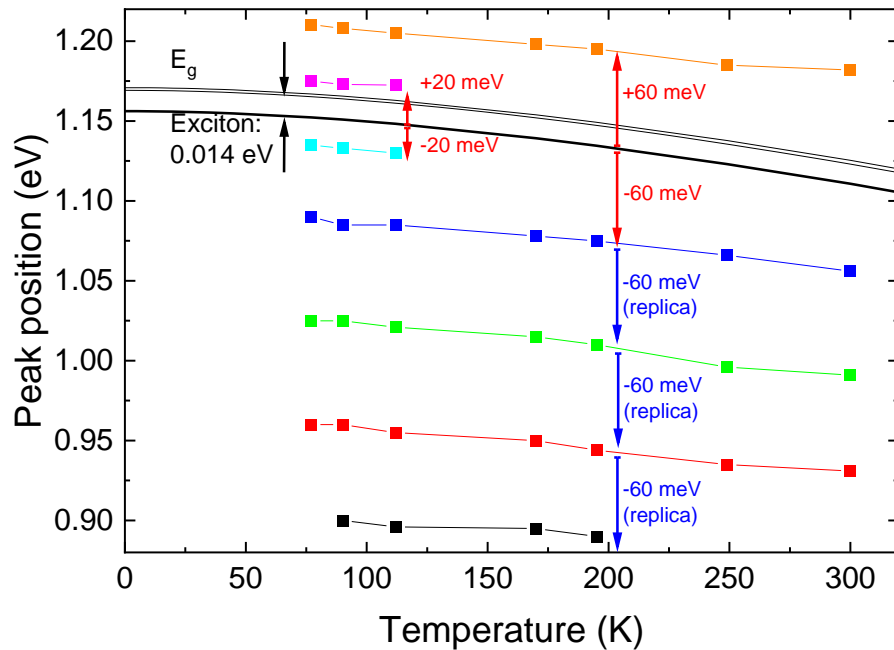


at low temperature:

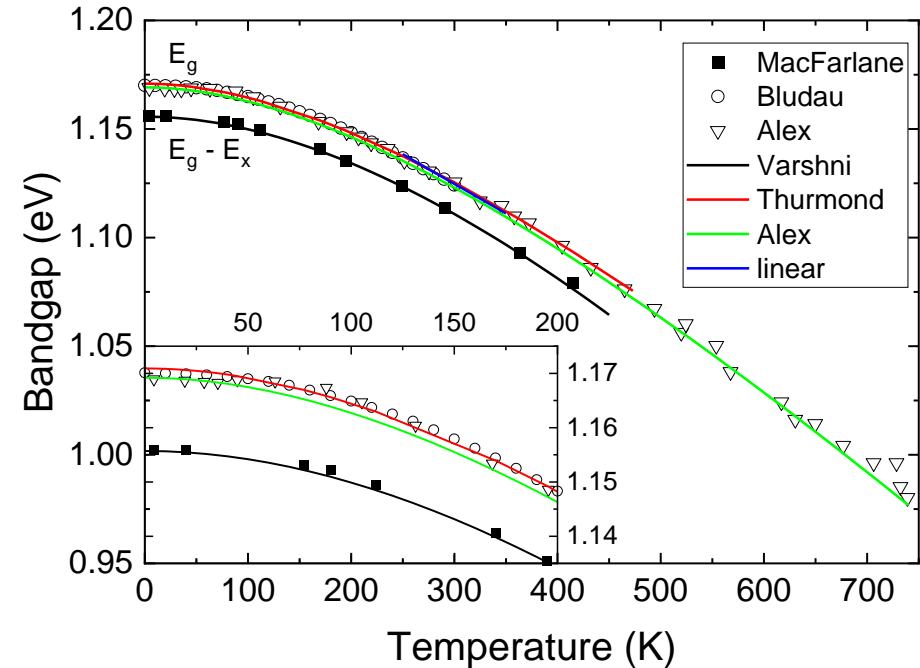
- Absorption drops massively (lattice must provide phonons)
- Steps become more prominent (less thermal broadening)
- Average slope changes (up to about 10 meV)

McFarlane, PR 1958
Daub, PRL 1995
Trupke, JAP 2003

Temperature dependence of E_g (c-Si)



Collect positions of phonon signatures



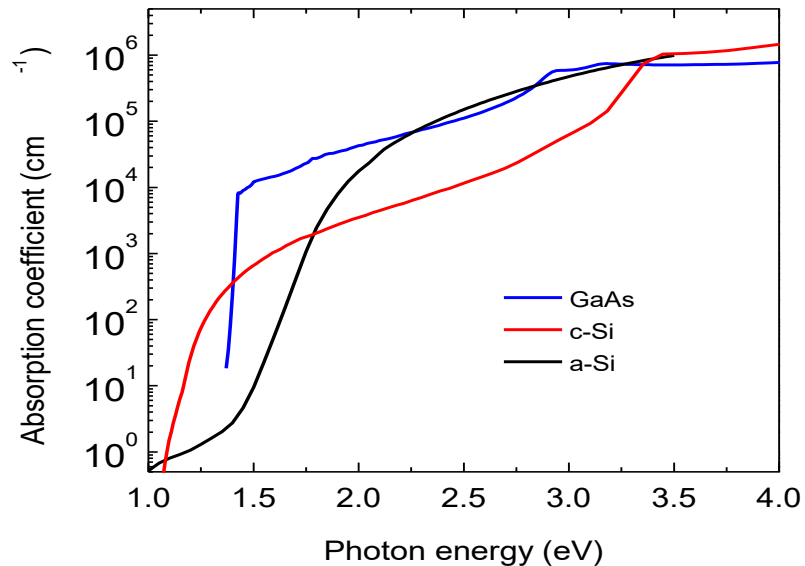
Empiric model:

$$E_g = 1.1557 - \frac{7.021 \times 10^{-4} \cdot T^2}{T + 1108} + E_{ex}$$

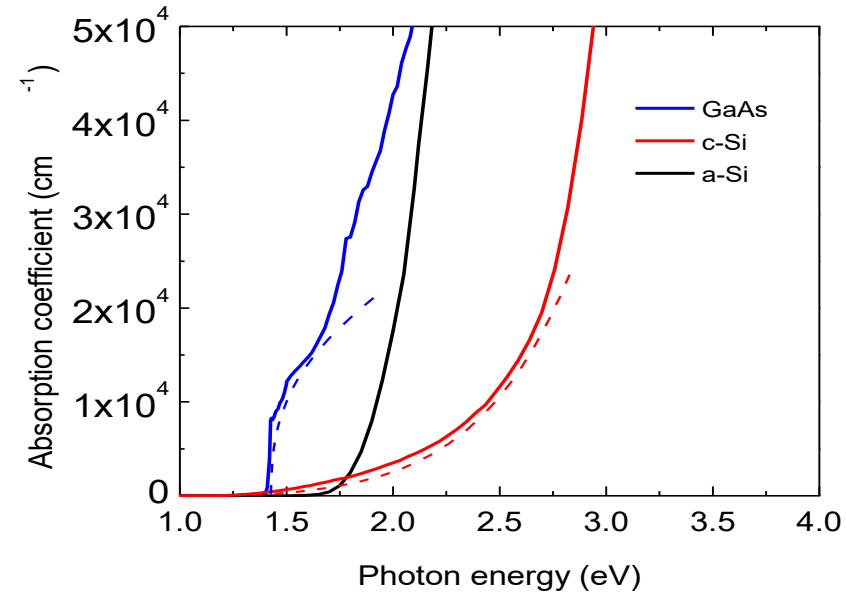
Varshni, physica (1967)

Absorption coefficient (summary)

logarithmic scale (usually shown)



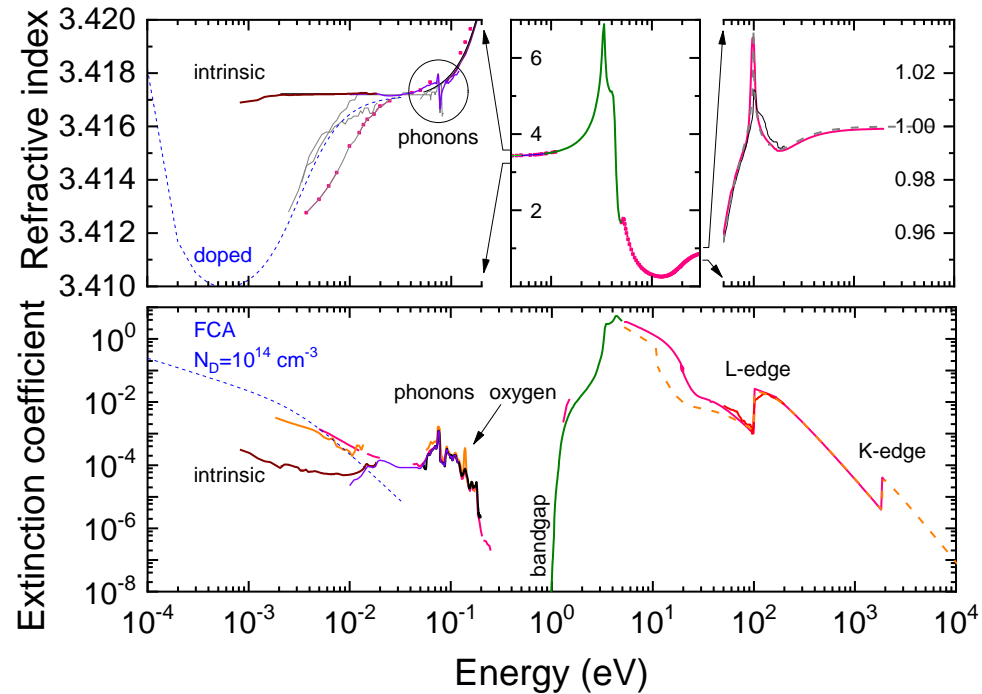
linear scale (clearer proportionality)



Direct: strong absorption close to gap $\alpha \sim (h\nu - E_g)^{\frac{1}{2}}$

Indirect gap: weak onset $\alpha \sim (h\nu - E_g)^2$, requires thick absorbers!

a-Si: essentially indirect



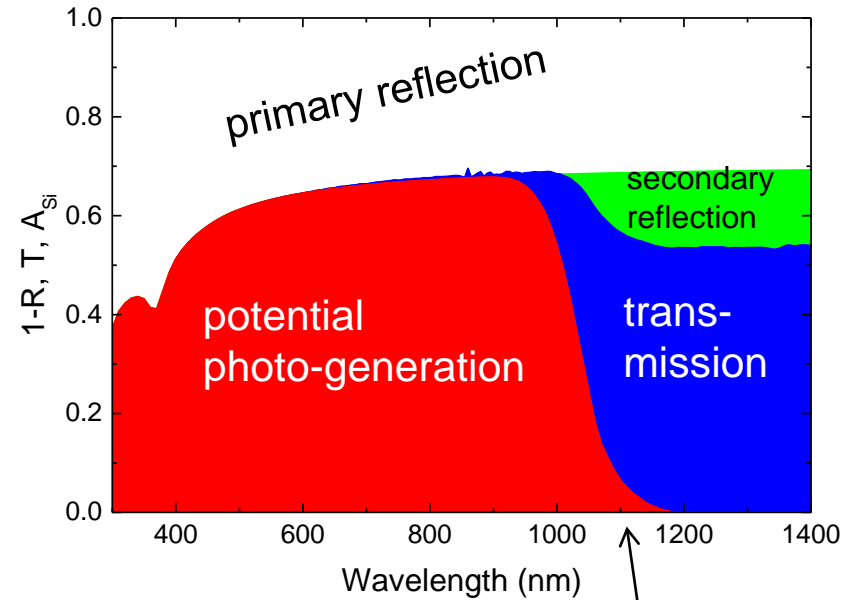
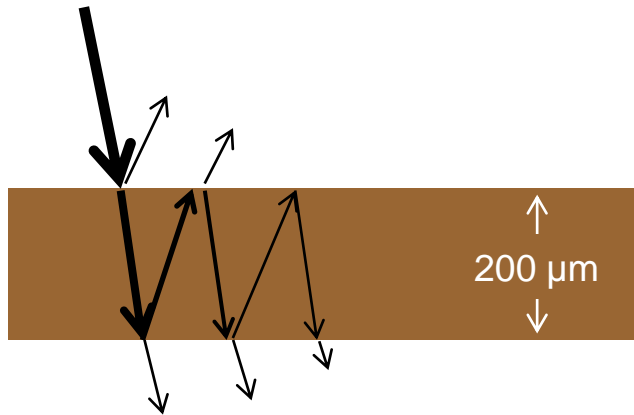
- Frequency dependence of contributions to polarizability arising from
- free electron plasma (depending on doping, can be up to vis)
 - lattice vibrations (IR)
 - displacement of electrons (vis and UV)
 - interactions with core electrons (X-ray regime)

Chandler, JAP, (2005)

Green, Sol. En. Mat. (2008)

Palik, Handbook of Opt. Const.

Absorption in a silicon slab

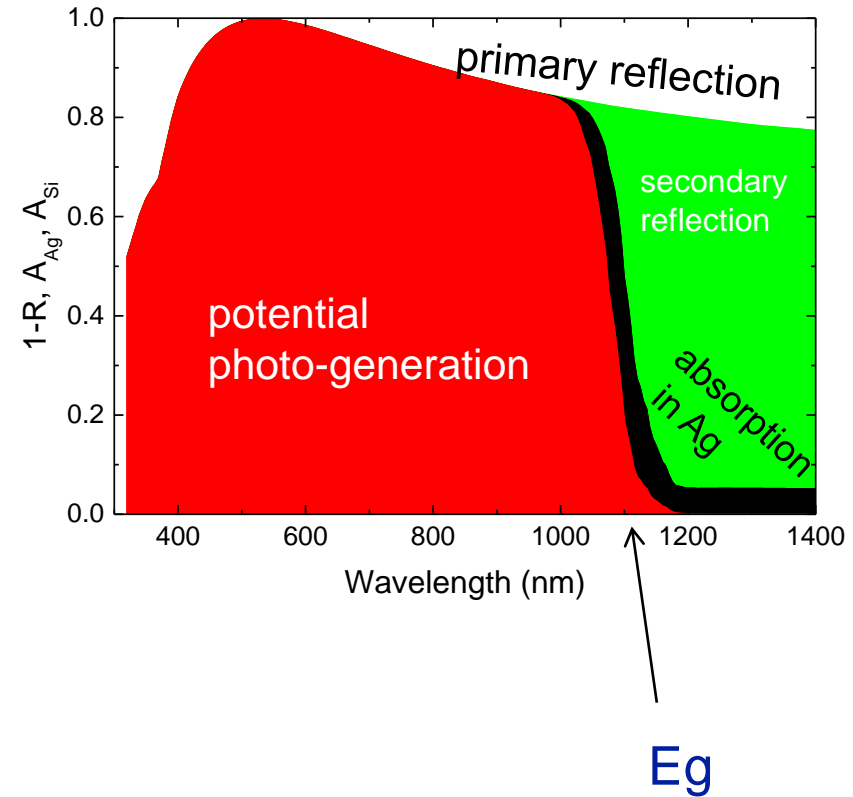
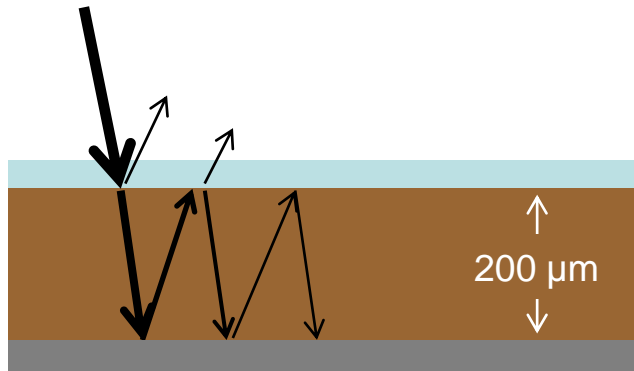


$$A = (1 - R) \left(\sum (1 - e^{-\alpha d}) + e^{-\alpha d} R (1 - e^{-\alpha d}) + e^{-2\alpha d} R^2 (1 - e^{-\alpha d}) + \dots \right)$$

$$= (1 - R) \frac{1 - e^{-\alpha d}}{1 - R e^{-\alpha d}}$$

- primary reflection (high refractive index) => needs AR functionality
- avoid transmission loss by rear reflector

EPFL Optical improvement



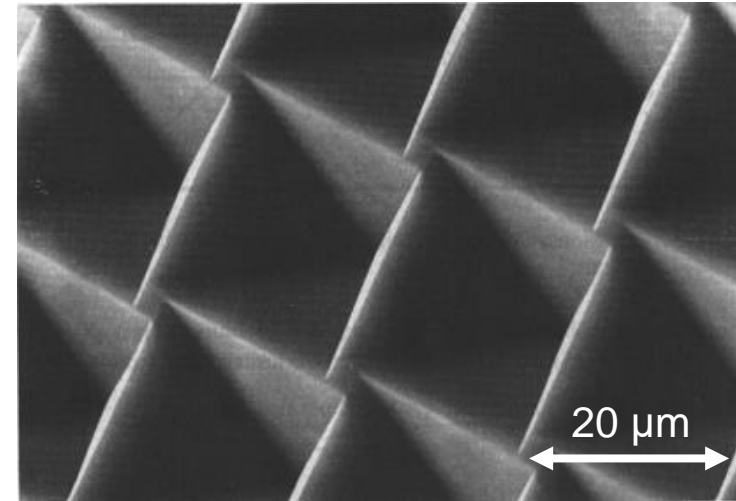
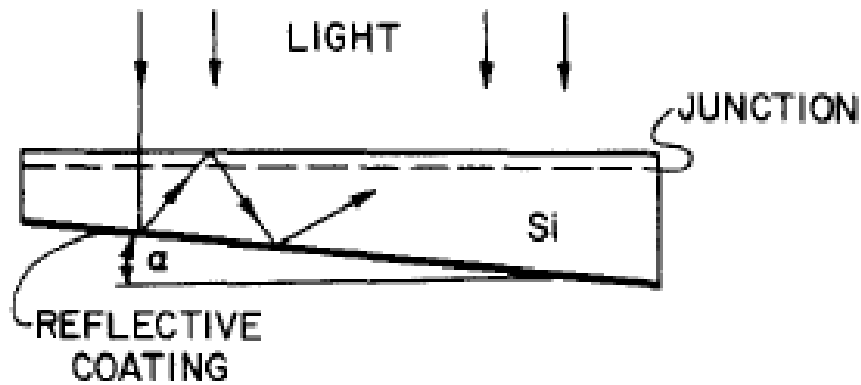
Add AR coating (70 nm, $n \approx 2$ at front)
Add reflector, eg. silver (at rear)

still significant loss due to low absorption
=> needs absorption enhancement

EPFL Enhancing absorption via prolonged light path

Total internal reflection
 $\theta_{\text{crit}} \approx 17^\circ$ ($n \approx 4$)

modern high eff. cells: inverted pyramids

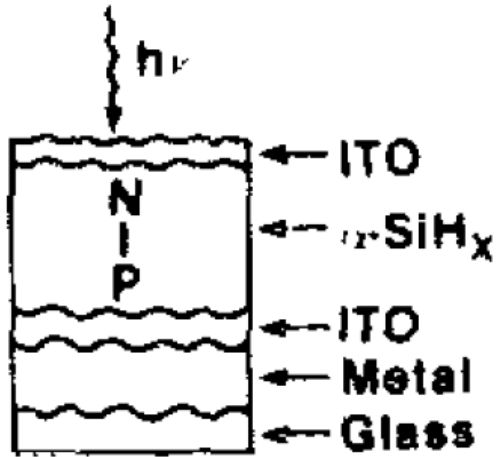


Apply geometric ray optics
for optimization

D. Redfield, Appl. Phys. Lett. (1974)

from Goetzberger, Sonnenenergie (1997)

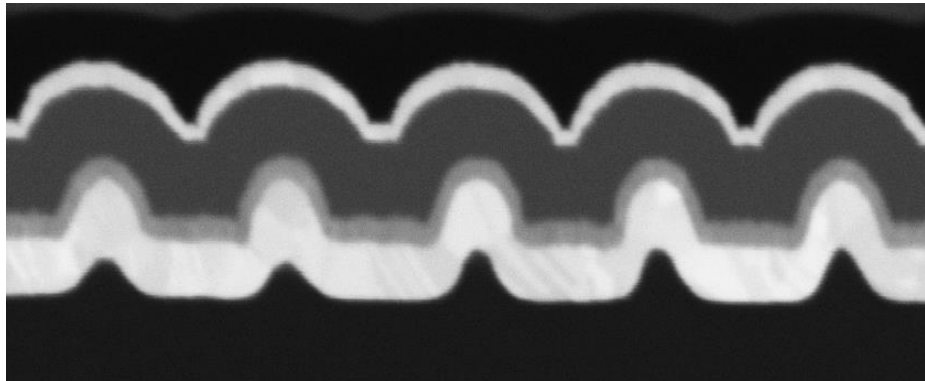
Thin cells: refraction → scattering



Reduce size of texture to film dimensions
 Transport texture from interface to interface
 (attention: texture gets modified by growth)

Deckman, JVST (1983)

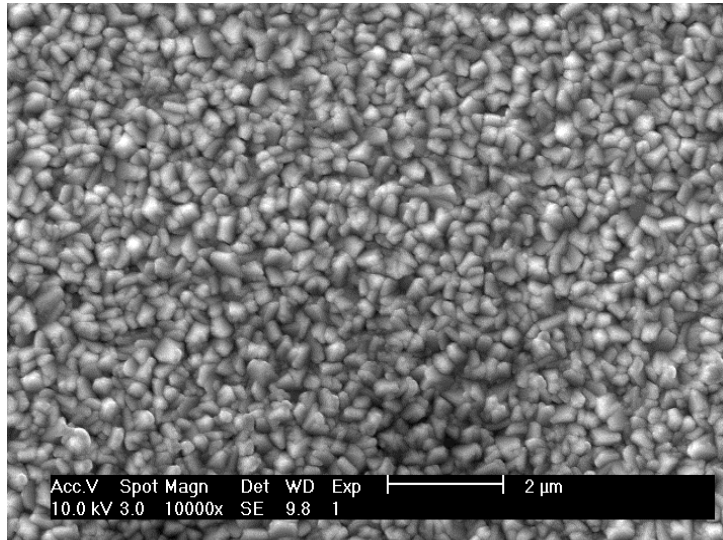
FIB cross-section through an n-i-p a-Si solar cell



- ITO
- a-Si (n-i-p sequence)
- ZnO buffer layer
- Ag electrode and reflector
- textured substrate

EPFL Randomly textured TCOs as growth template

SnO₂:F (Asahi-U)

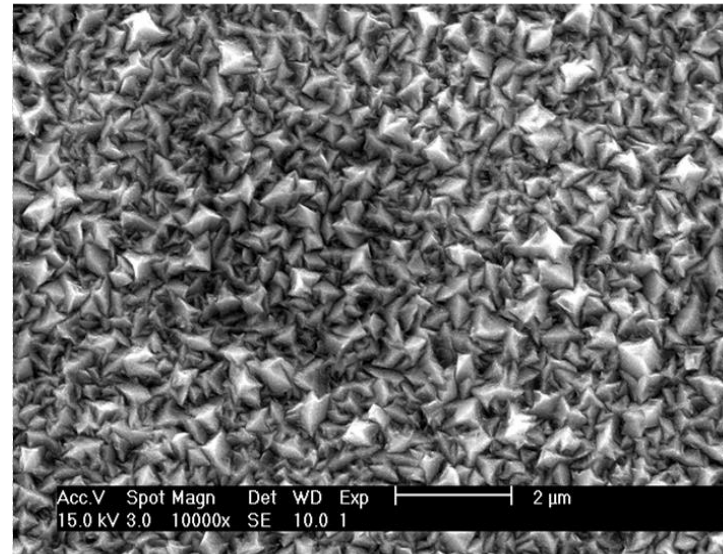


Atmospheric pressure CVD
(AP-CVD)



Sato, Asahi Res. Rep. (1990)
Kambe, 3rd World PV Conf (2003)

LP-CVD ZnO:B (Z2)

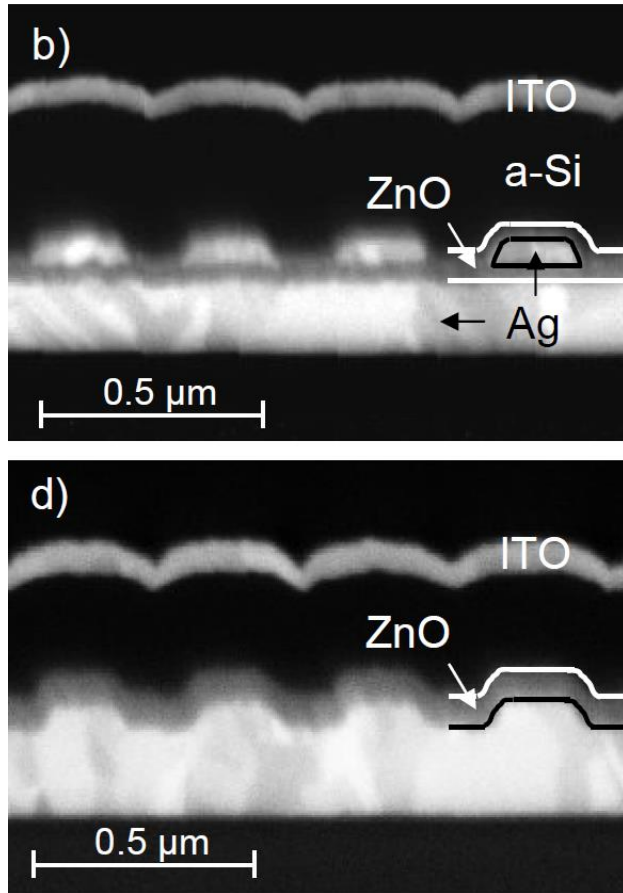


Low pressure CVD
(LP-CVD)

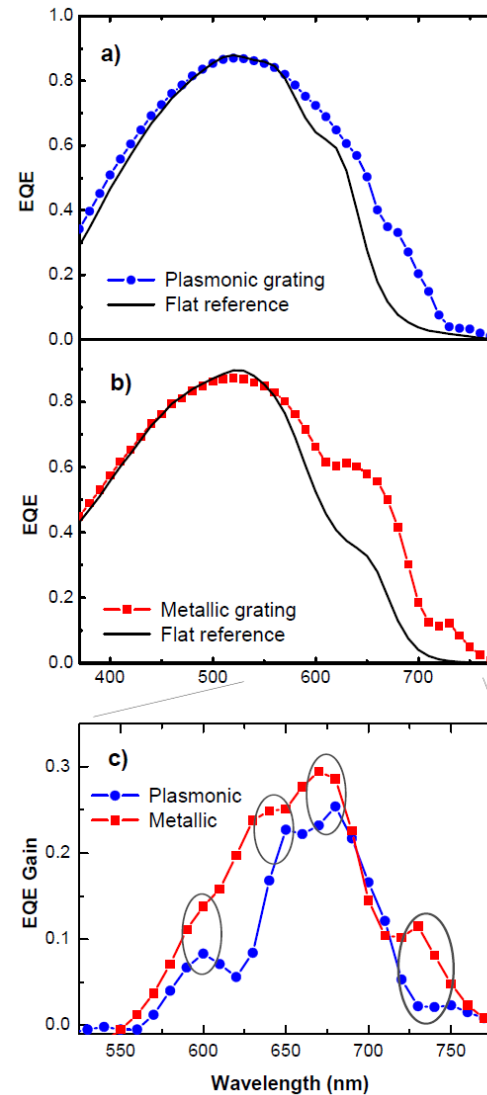


W. Wenas, Jap. J. Appl. Phys (1991)
S. Faÿ, EU PV Conf. (2000)

EPFL Scattering particles (here: in the back contact)



identical absorber geometry,
plasmonic performance not (yet?)
beyond “classic” structure



C. Pahud, IEEE JPV, (2012)

- Enhanced optics (general)
 - AR coating (interference or by index grading)
 - reduce parasitic losses (contact layers with higher gaps)
- Enhanced absorption by scattering (needed for weakly absorbing cells, either indirect gap, or thin cells)
 - textures (proven for Si-based cells)
 - nanowires (so-so)
 - plasmonic scattering (theoretically interesting, but parasitic absorption)